



€ MRS 2022 Fall Meeting

19th - 22nd September 2022

Free-standing InSb nanostructures: growth, morphology control and electrical characterization

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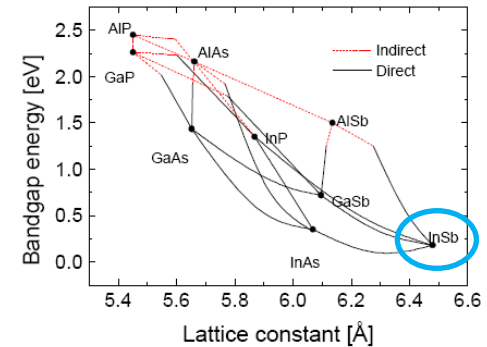
Outline

- **InSb nanostructures:** motivation and challenges
- **InSb morphology control** on InAs nanowire stems: nanowires (1D), nanoflags (2D), nanocubes (3D)
- **Directional growth:** results and modelling
- **InSb nanoflags:** structural and electrical properties

Motivation

InSb:

- Small bandgap, low electron effective mass, high electron mobility, high Landè g-factor and strong spin-orbit interaction
→ promising material for optoelectronics, thermoelectrics, spintronics and quantum computing

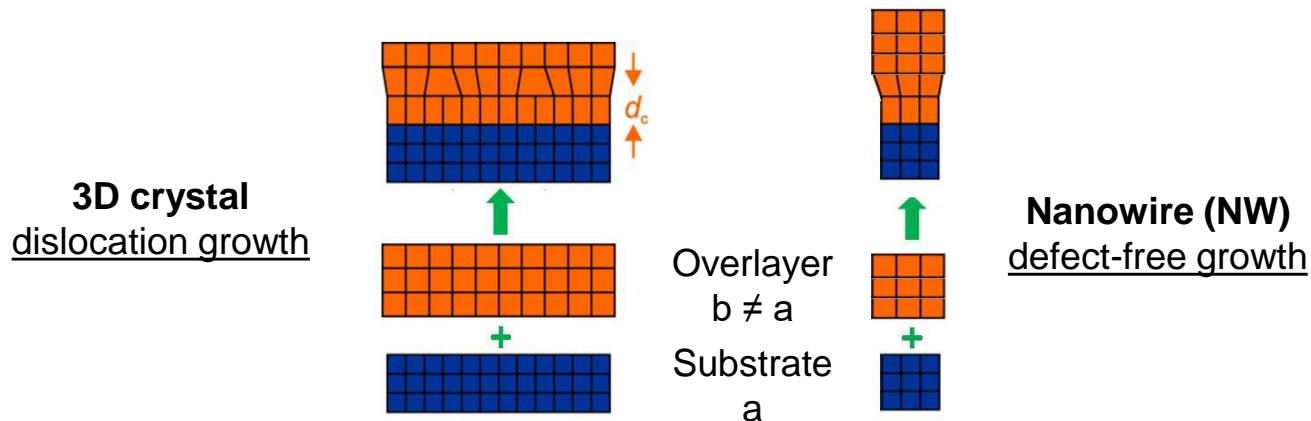


- Large lattice mismatch with all other III-Vs → difficult integration of defect-free InSb in planar epitaxy
- Sb acts as a surfactant → difficult to control/tune the InSb morphology during the growth

Free-standing InSb nanostructures:

- ✓ Defect-free growth of heterostructures
- ✓ High surface/volume ratio
- ✓ Carriers confinement

Heteroepitaxy: bulk crystal vs nanostructures



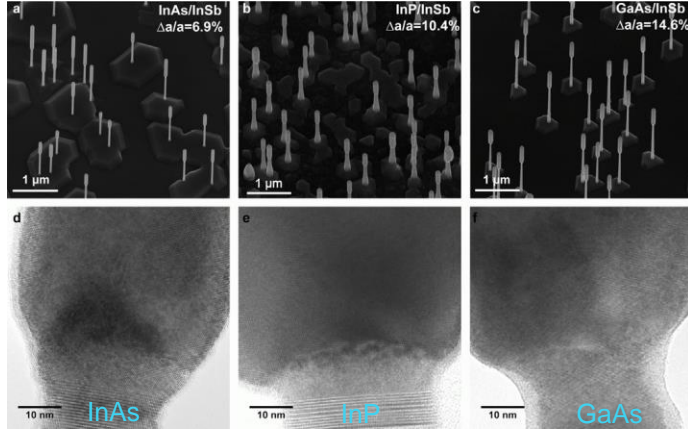
Motivation

Free-standing InSb nanostructures (1D)

InSb heterostructure nanowires: MOVPE growth under extreme lattice mismatch

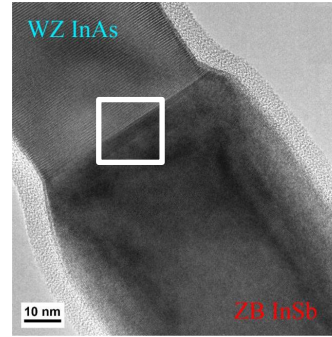
Nanotechnology
20 (2009) 495606

Philippe Caroff[†], Maria E. Messing, B. Matthias Borg,
Kimberly A. Dick, Kunt Deppert and Lars-Erik Wernersson



InAs/InSb nanowire heterostructures grown by chemical beam epitaxy

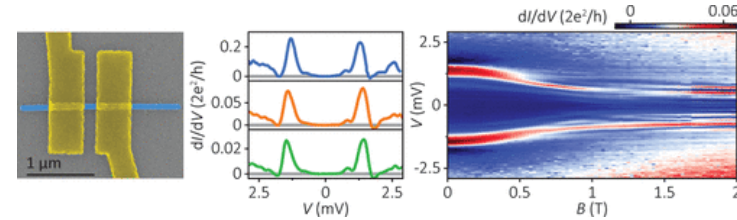
Daniele Ercolani[†], Francesca Rossi[‡], Ang Li[†], Stefano Roddaro[†],
Vincenzo Grillo[†], Giancarlo Salviati[†], Fabio Beltram[†] and
Lucia Sorba[†]



Nanotechnology
20 (2009) 505605

Hard Superconducting Gap in InSb Nanowires

Önder Gül,^{†,‡,§} Hao Zhang,^{†,‡} Folkert K. de Vries,^{†,‡} Jasper van Veen,^{†,‡} Kun Zuo,^{†,‡} Vincent Mourik,^{†,‡}
Sonia Conesa-Boj,^{†,‡} Michal P. Nowak,^{†,‡,§} David J. van Woerkom,^{†,‡} Marina Quintero-Pérez,^{†,||}
Maja C. Cassidy,^{†,‡} Attila Geresdi,^{†,‡} Sebastian Koelling,^{†,§} Diana Car,^{†,‡,||} Sébastien R. Plissard,^{†,||,¶}
Erik P. A. M. Bakkers,^{†,||,¶} and Leo P. Kouwenhoven^{†,‡,¶}

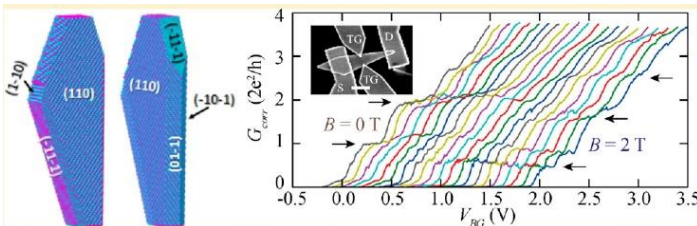


Nano Lett. 17 (2017), 4, 2690–2696

(2D)

Twin-Induced InSb Nanosails: A Convenient High Mobility Quantum System

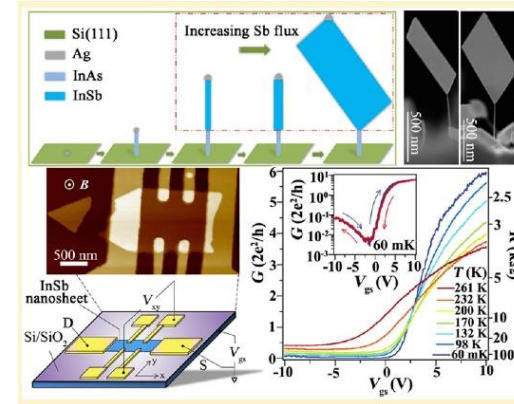
María de la Mata,[†] Renaud Leturcq,^{*,‡,§} Sébastien R. Plissard,^{||} Chloé Rolland,^{*} César Magén,[⊥]
Jordi Arbiol,^{*,§,¶,||} and Philippe Caroff^{*,‡,¶,||}



Nano Lett. 16 (2016) 825

Free-Standing Two-Dimensional Single-Crystalline InSb Nanosheets

D. Pan,[†] D. X. Fan,[‡] N. Kang,[‡] J. H. Zhi,[‡] X. Z. Yu,[†] H. Q. Xu,^{*,‡} and J. H. Zhao^{*,†}

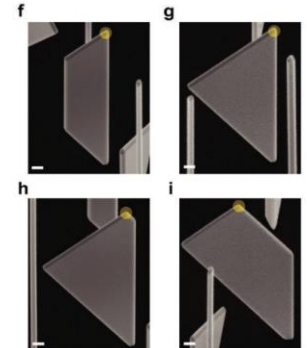


Nano Lett. 16 (2016) 834

Bottom-Up Grown 2D InSb Nanostructures

Sasa Gazibegovic,^{*} Ghada Badawy,^{*} Thijs L. J. Buckers, Philipp Leubner, Jie Shen,
Folkert K. de Vries, Sebastian Koelling, Leo P. Kouwenhoven, Marcel A. Verheijen,
and Erik P. A. M. Bakkers

Adv. Mater. 31
(2019) 1808181



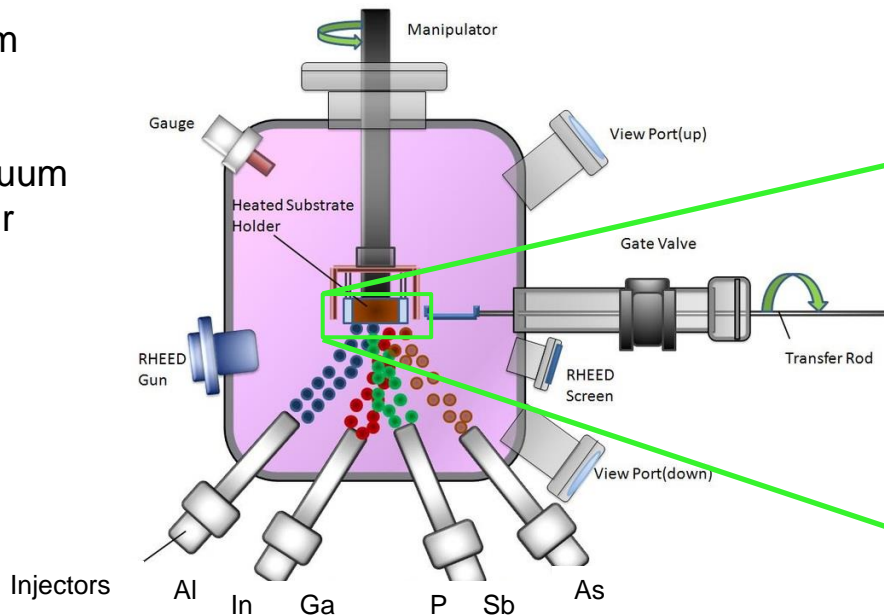
Our approach

OUR GOALS: - morphology control of high quality InSb nanostructures by tuning the growth parameters
- develop a directional growth protocol to achieve free standing InSb nanoflags on NW stems

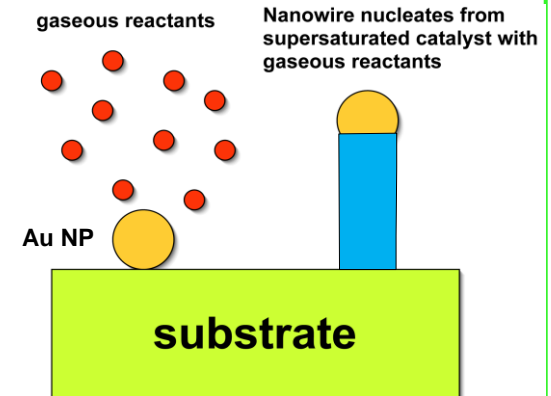
OUR APPROACH: Au assisted Chemical Beam Epitaxy using Au nanoparticle from colloidal solutions

Chemical Beam Epitaxy (CBE)

Ultra High Vacuum (UHV) chamber



Nanoparticle (NP) assisted vapour-liquid-solid (VLS) mechanism



VLS growth occurs when a liquid alloy droplet starting from a metal nanoparticle (NP) becomes supersaturated with material from a gaseous reactant. The material then precipitates from the solid-liquid interface to form a nanowire.

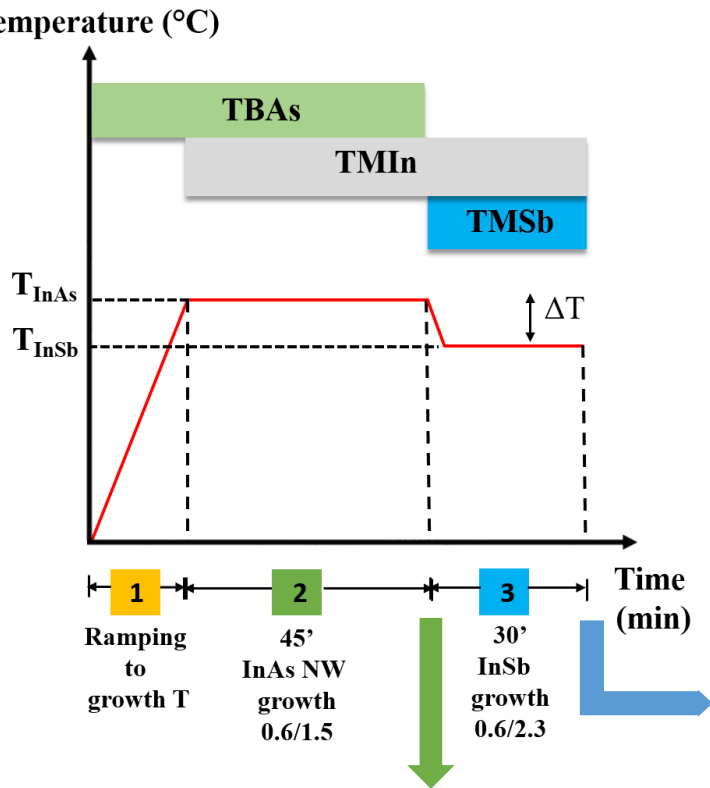


CBE at NEST: Riber Compact-21 CBE system
Metal-organic precursors:
Group III : TMI_n, TEGa, TMAI
Group V : TBAs, TBP, TDMASb, TMSb
n-doping: TBSe

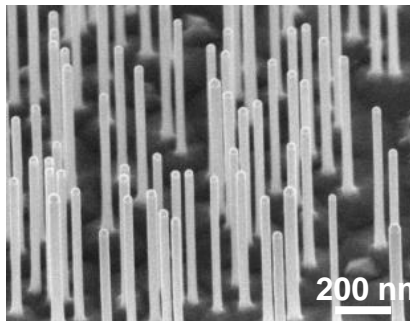
Morphology control of InSb nanostructures

Substrates: InAs (111)B, Au nanoparticles: 30 nm colloids
MO precursors: TBAs, TMIIn, TMSb. Sample rotation: 5 rpm

InSb growth: T optimization

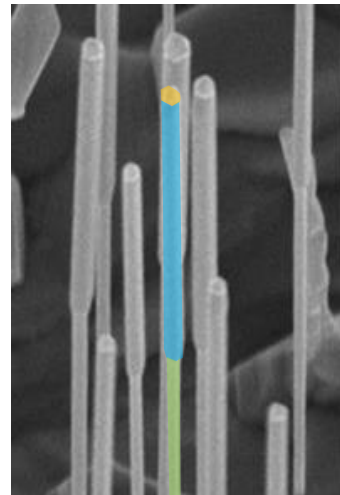


InAs nanowire stems



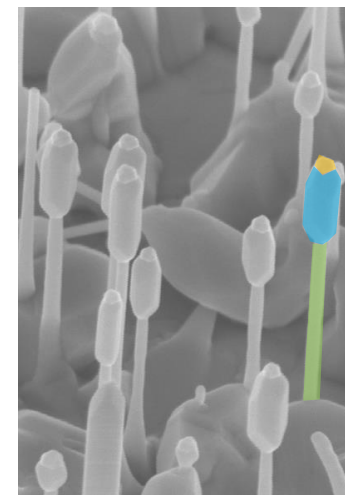
$T_{InAs} : 385^{\circ}C$

$\Delta T = -20^{\circ}C$

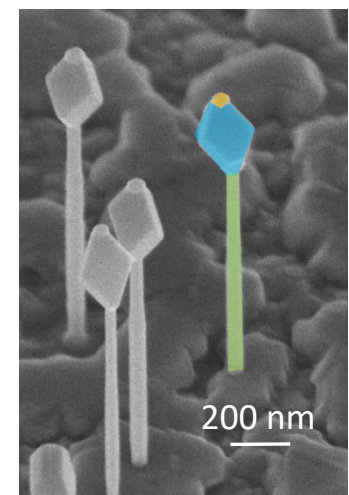


**1D- like
Nanowires**

$\Delta T = -30^{\circ}C$



$\Delta T = -40^{\circ}C$

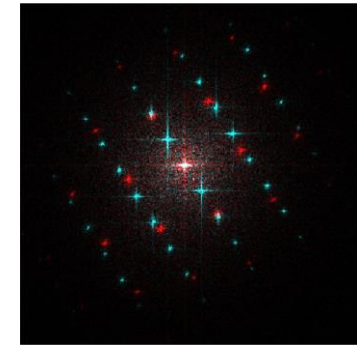
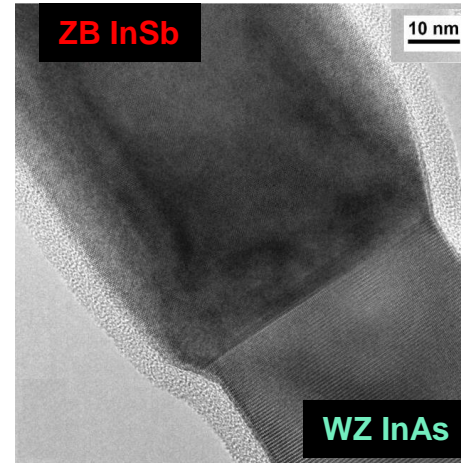
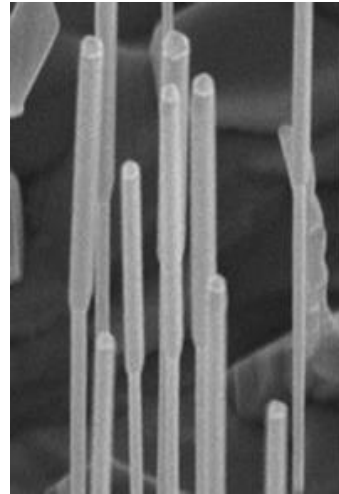
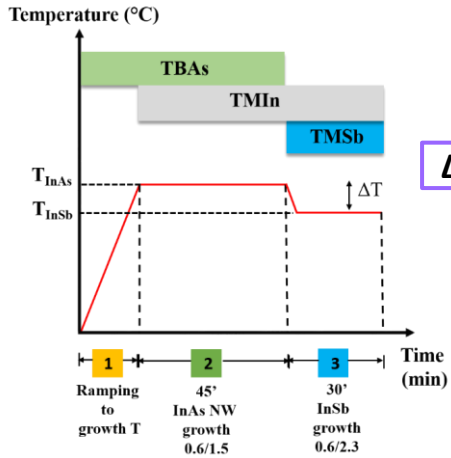


**3D- like
Nanocubes**

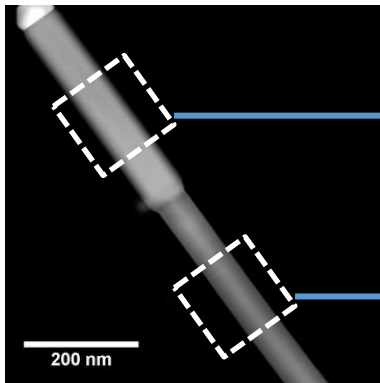
**Low T enhances the radial growth
and reduces the axial growth**

InSb nanowires

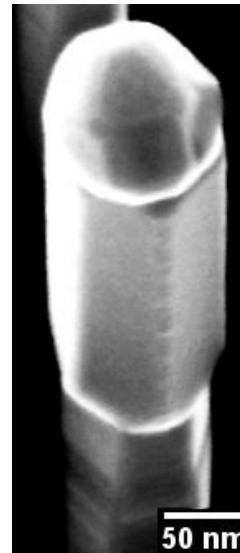
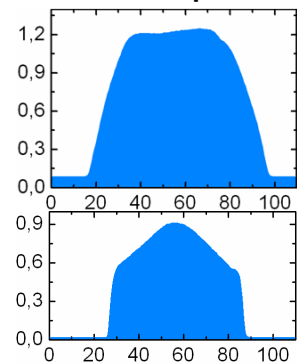
With sample rotation uniform InSb growth



InSb: $\langle 110 \rangle$ zone axis
InAs: $\langle 2-1-10 \rangle$ zone axis



HAADF profile



Top-view: NW cross-section



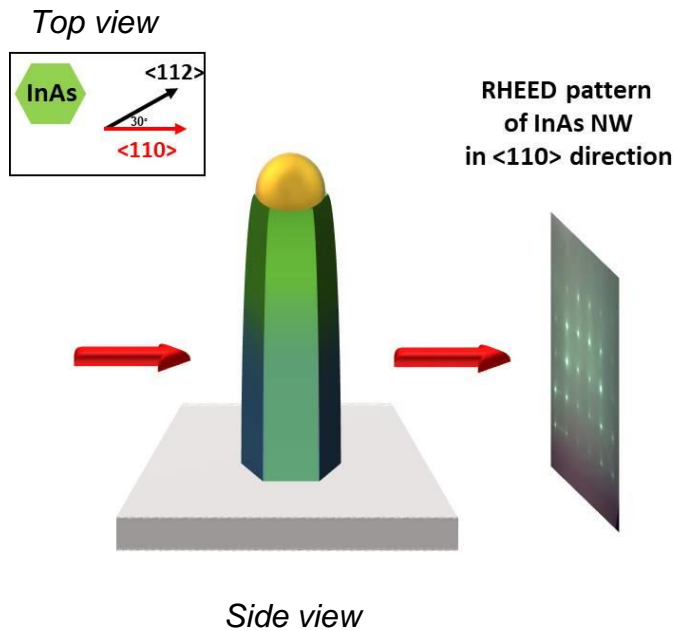
- InAs NWs have WZ crystal structure with 6 equivalent $\{112\}$ sidewalls
- InSb has ZB crystal structure with 6 equivalent $\{110\}$ sidewalls

D. Ercolani et al. *Nanotechnology* 20, 505605 (2009)

L. Lugani et al. *Cryst. Growth Des.*, 10, 4038 (2010)

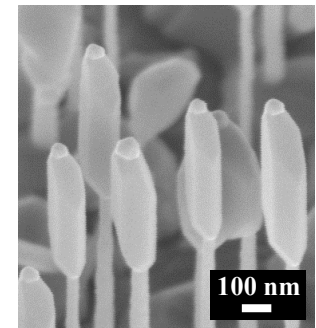
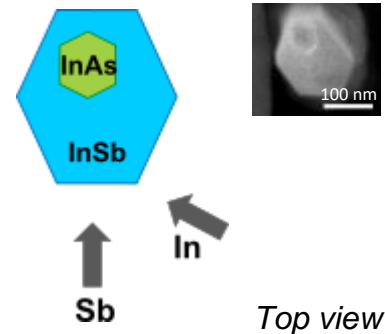
Directional InSb radial growth

Sample alignment
before InSb growth:

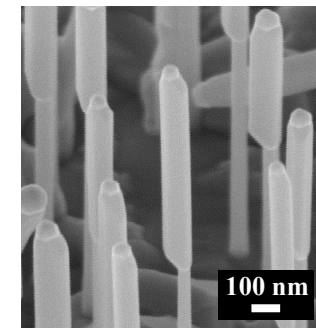
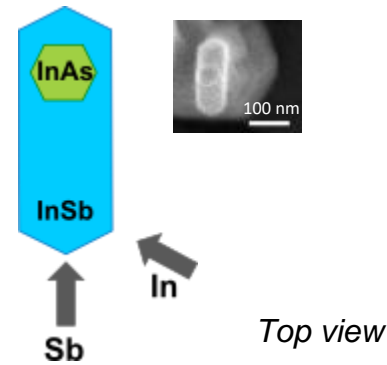


InSb growth at $\Delta T -30^\circ\text{C}$ with NO sample rotation:

Sb beam projection
aligned to $\{110\}$ direction

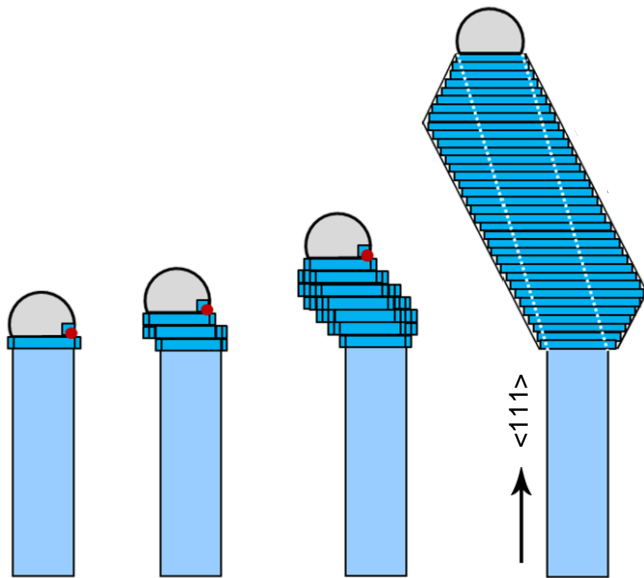
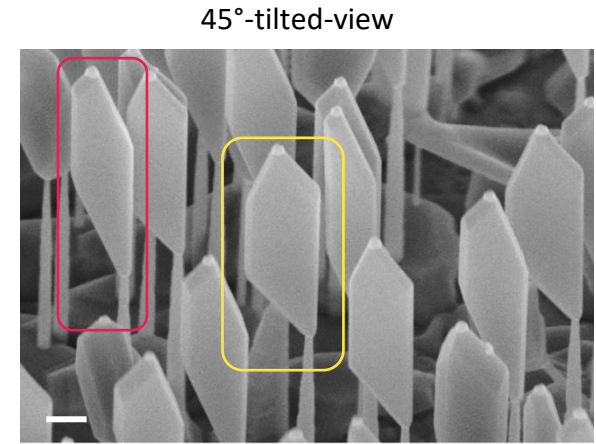
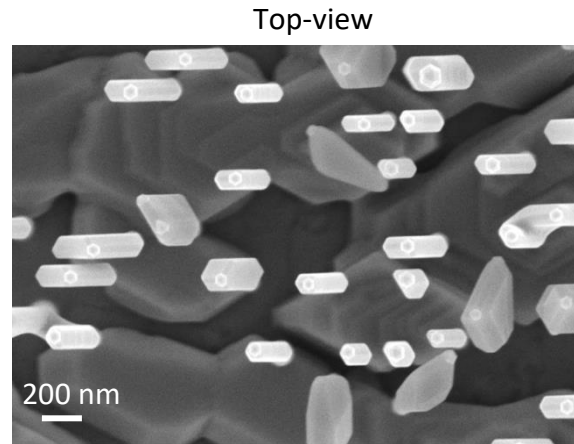
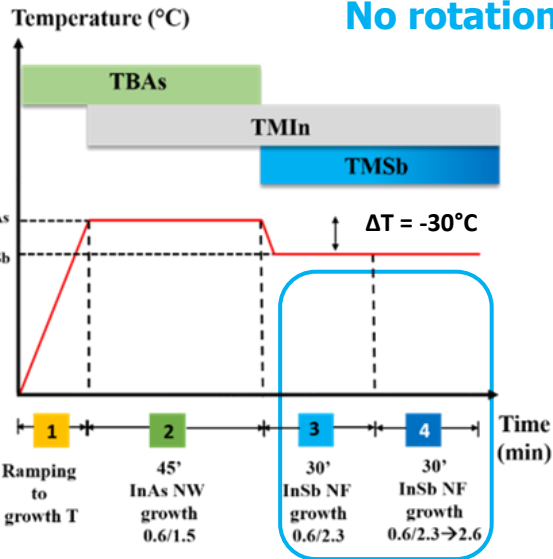


Sb beam projection
aligned to $\{112\}$ direction



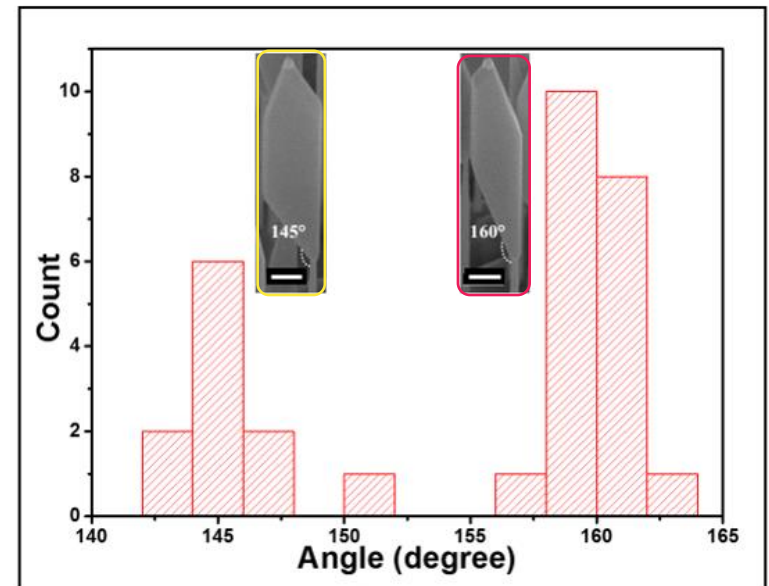
Free-standing InSb nanoflags (NFs)

No rotation, alignment, increasing Sb flux \rightarrow asymmetric growth enhancement

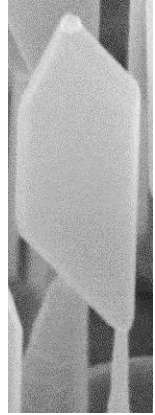
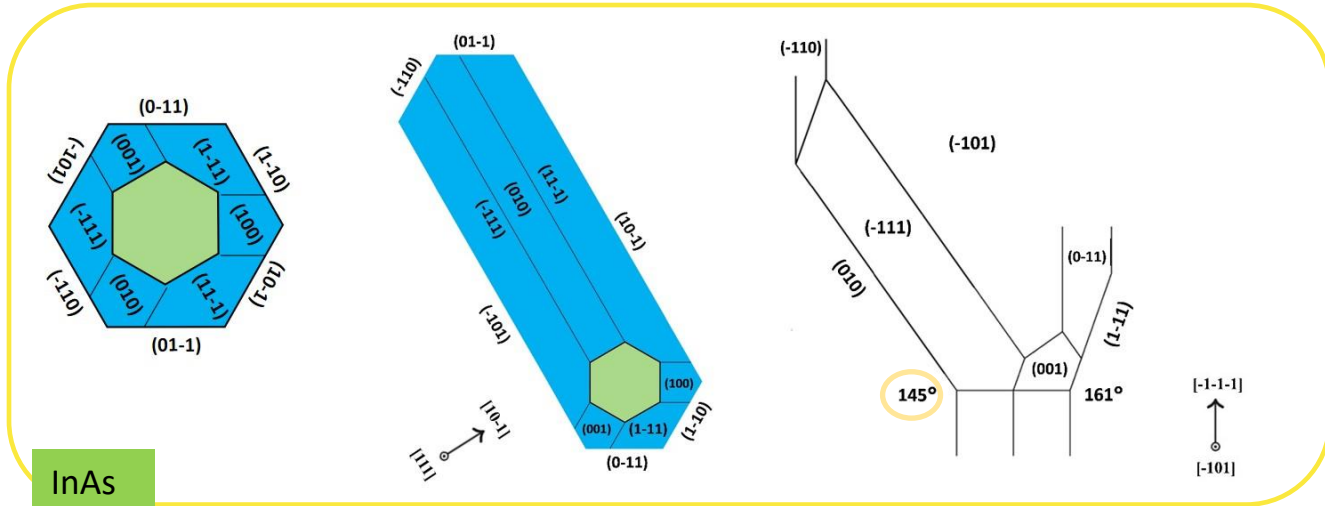


NF final shape is the result of the combined axial VLS growth and anisotropic radial growth, together with the mobility of the droplet (due to the high Sb flux), which crawls from left to right or right to left, along the direction of triple phase line.

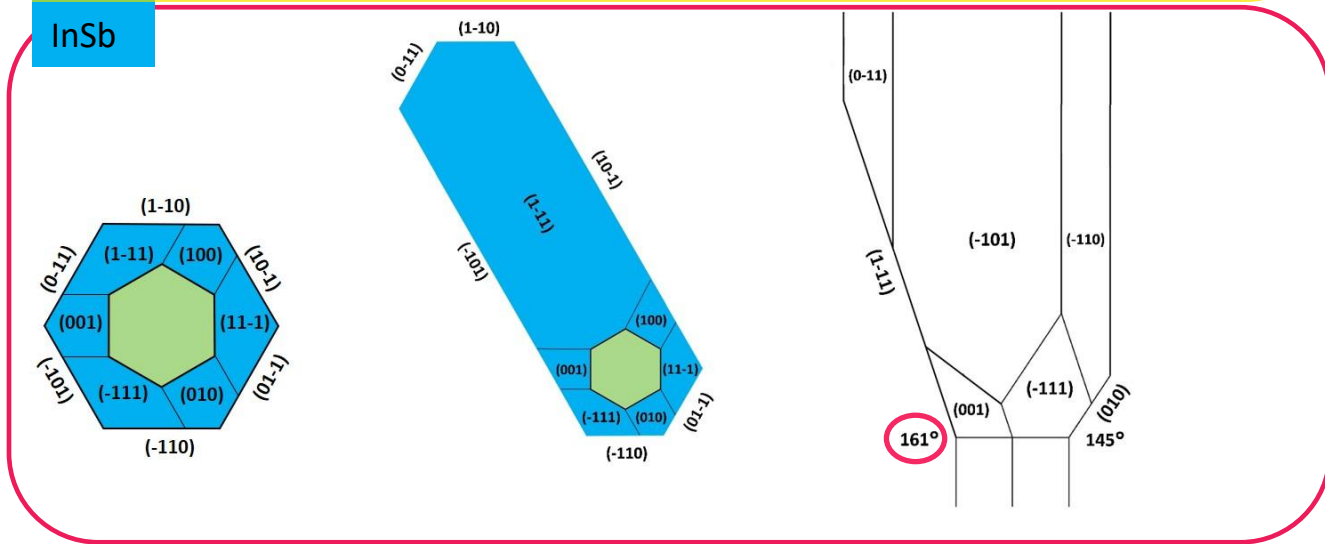
2 different aperture angles: 145° and 160°



Free-standing InSb nanoflags (NFs)



InAs
InSb



180° rotation
around the
growth axis of
the additional
facets at the
interface

**SYMMETRIC NW
TOP VIEW**

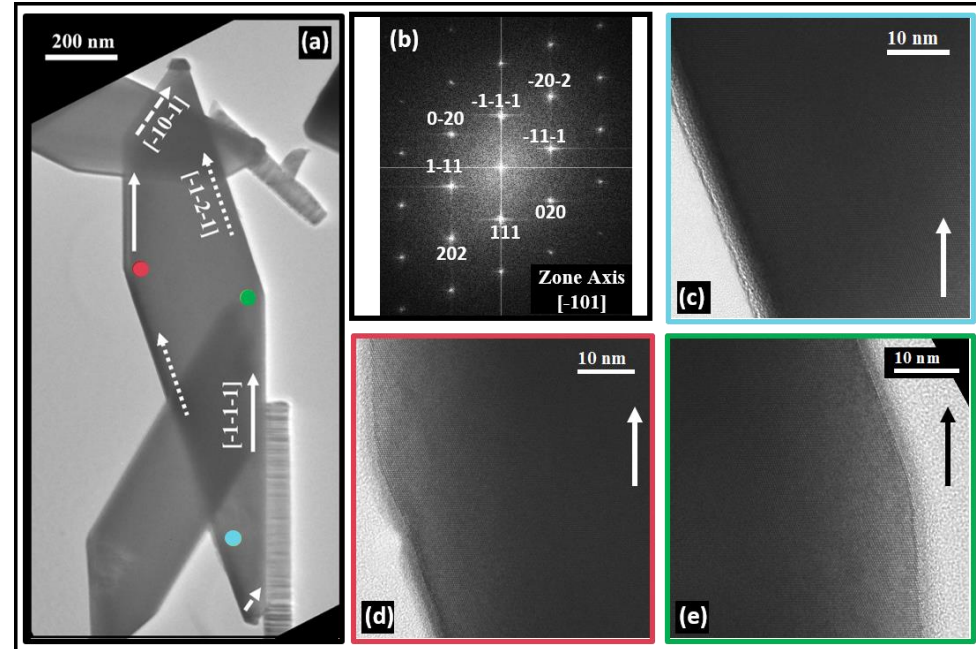
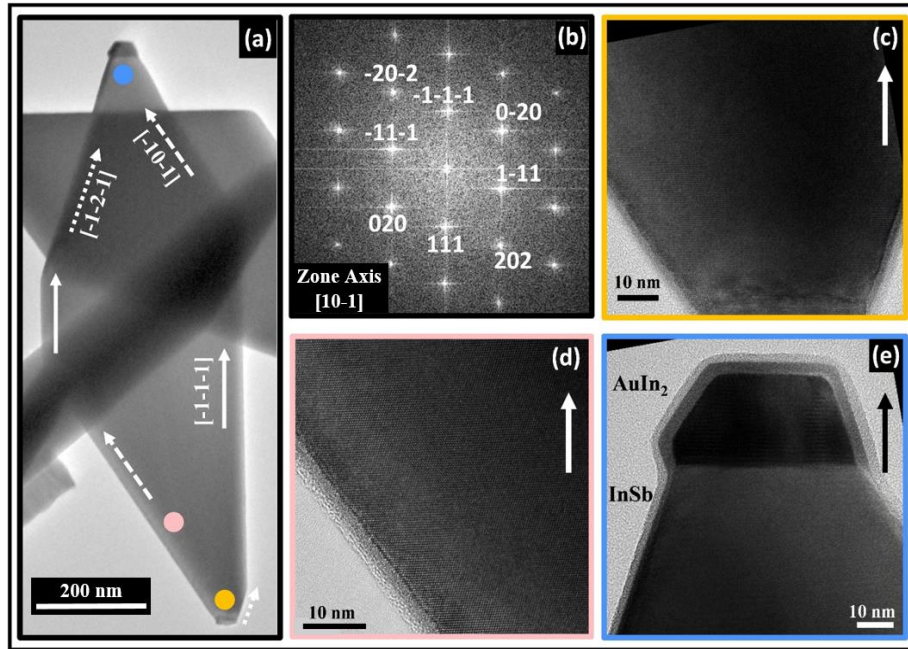
**NANOFLAG
TOP VIEW
<111> projection**

**NANOFLAG
SIDE VIEW
<100> projection**

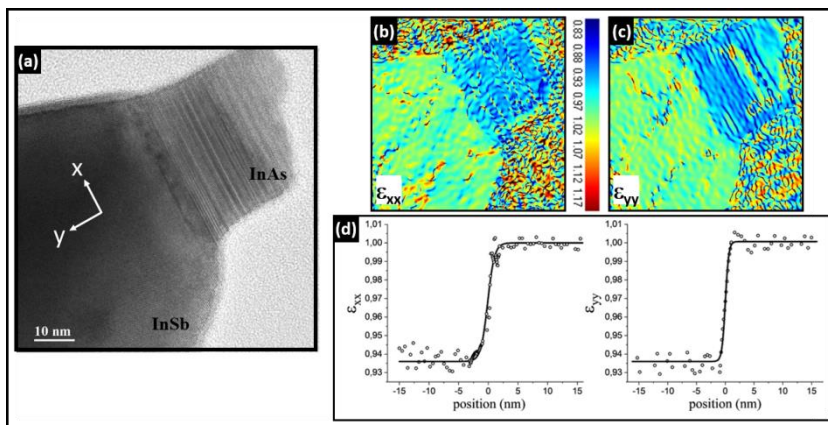
Free-standing InSb nanoflags (NFs)

145° aperture angle

160° aperture angle

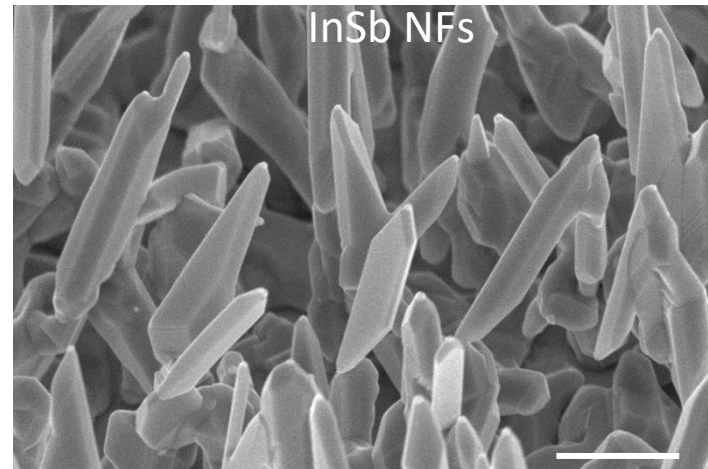
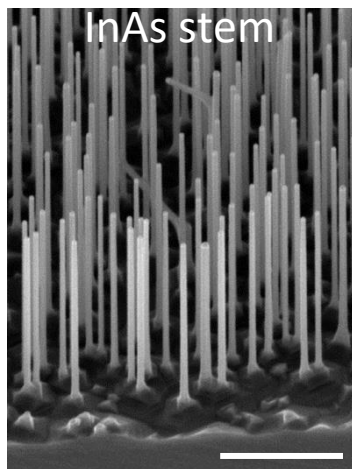
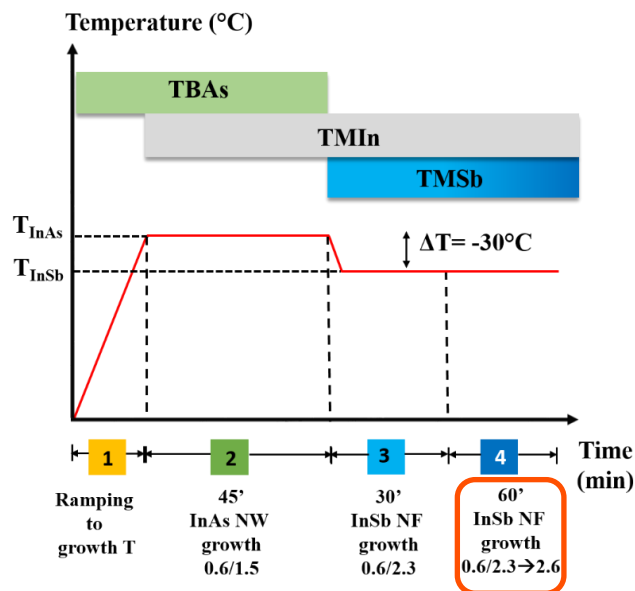


GPA



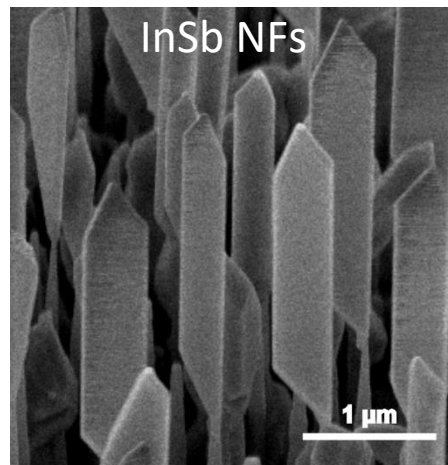
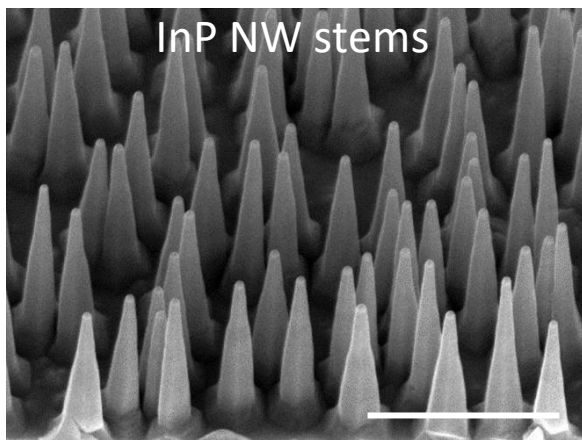
- Defect-free ZB crystal structure
- Stoichiometric composition
- Relaxed lattice parameter
- Still too small for practical use (multi-contact devices)

Longer InSb growth time



InAs stem bending and TMSb etching

Increasing InSb growth time

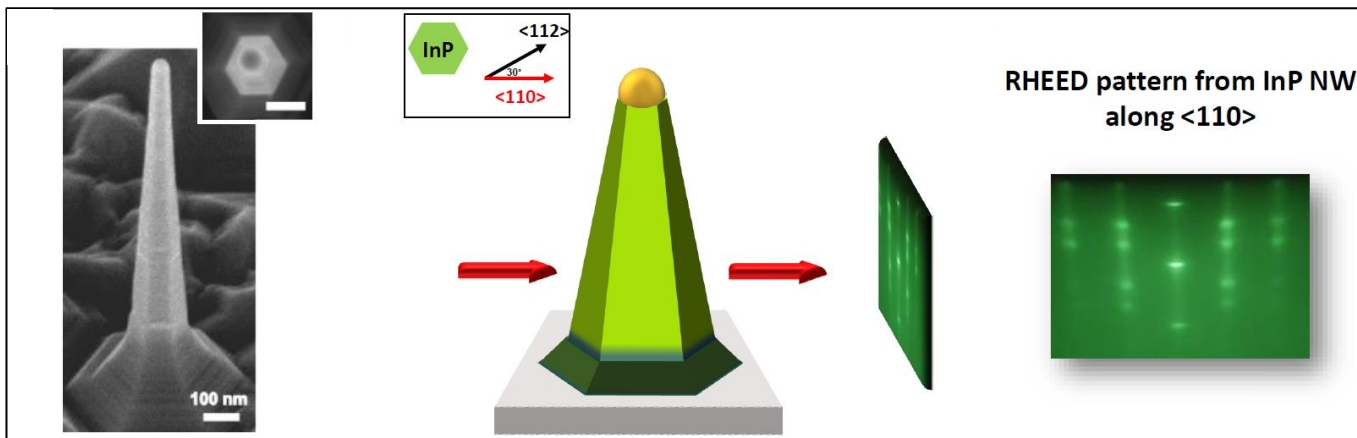


InSb NFs dimension
 Length= $2.8 \pm 0.2 \mu m$
 Width= $470 \pm 80 \text{ nm}$
 Thickness= $105 \pm 20 \text{ nm}$

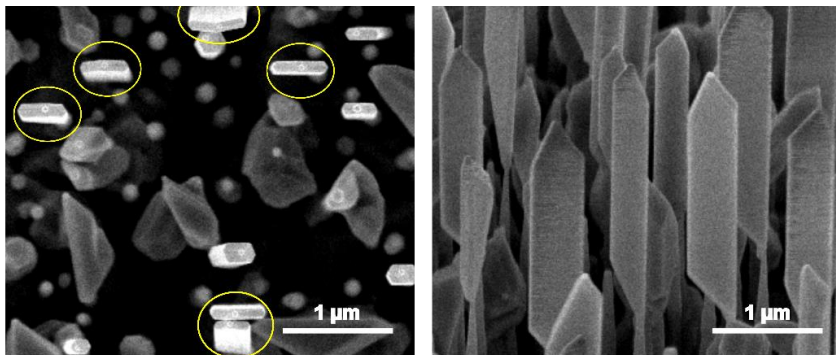
Using tapered and more robust InP NW stems, we could achieve bigger InSb NFs

Larger InSb nanoflags

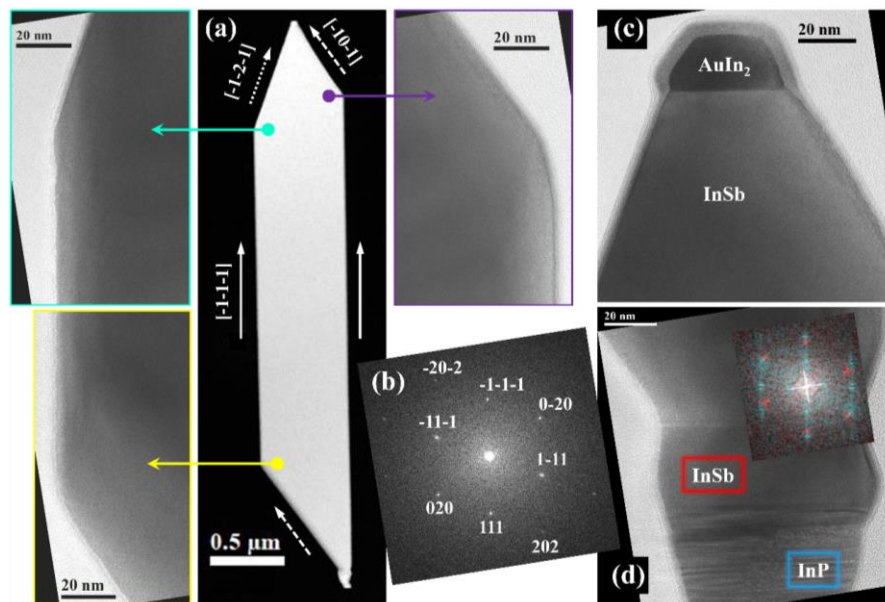
InP NWs have mixed WZ/ZB crystal structure, but still $\langle 112 \rangle$ sidewalls



Sb beam projection aligned to $\{112\}$ direction



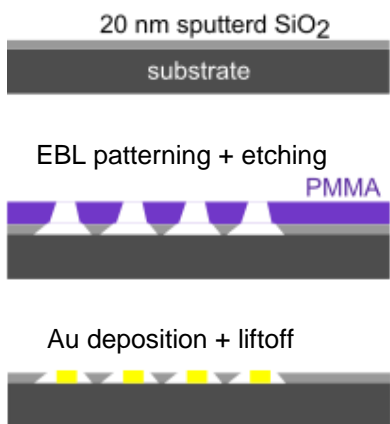
Lower yield, but bigger NFs



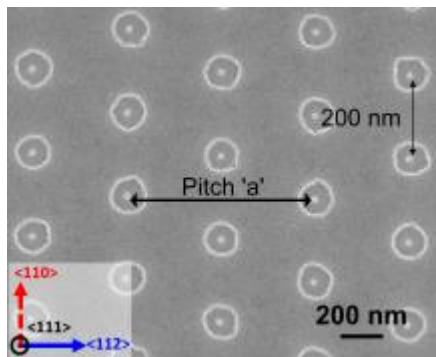
STEM-HAADF image and corresponding HRTEM images show **defect-free InSb ZB crystal structure**.

Morphological evolution of InSb NFs in regular arrays

Substrate preparation



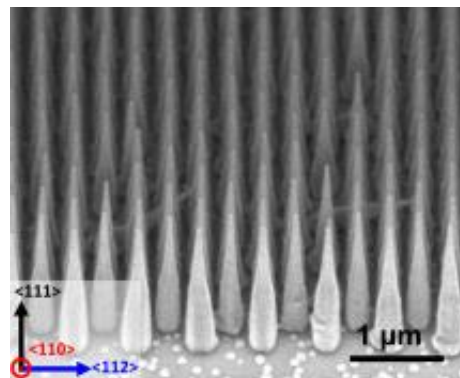
Top view SEM image



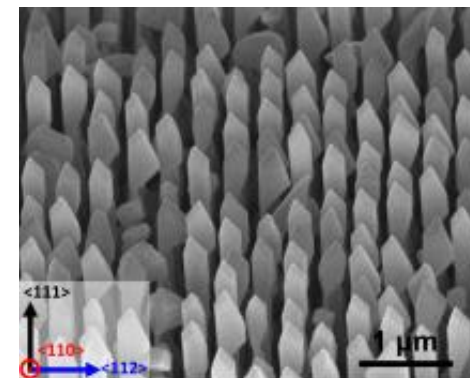
Pitch 'a': 500, 700, 900, 1100 and 1500 nm.

Selective area + VLS directional growth

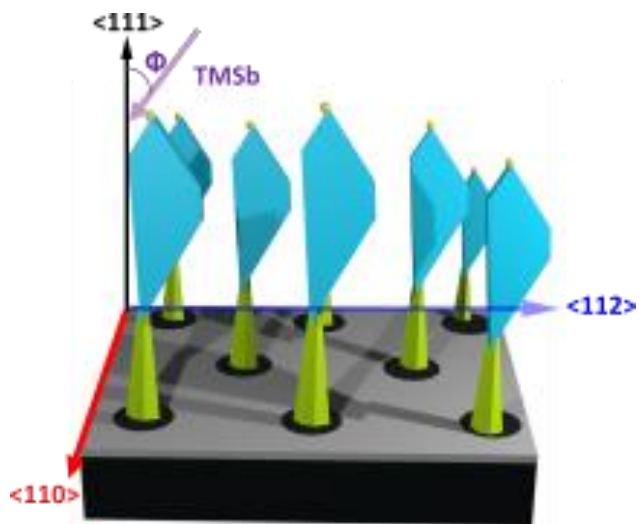
InP nanowire stems



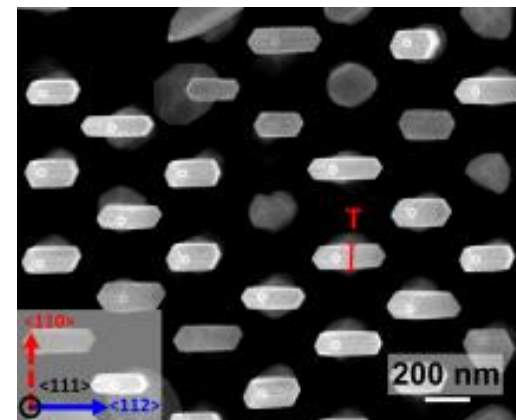
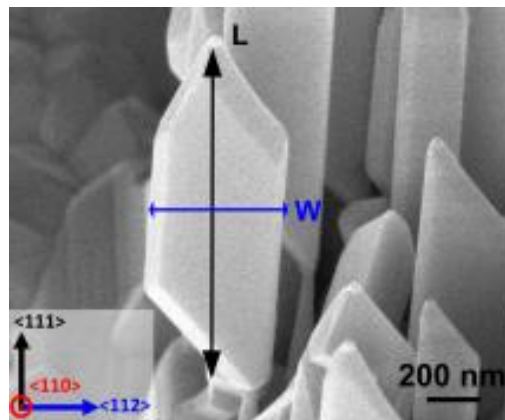
InSb nanoflags



Pitch AND Sb projection in $\langle 112 \rangle$ direction



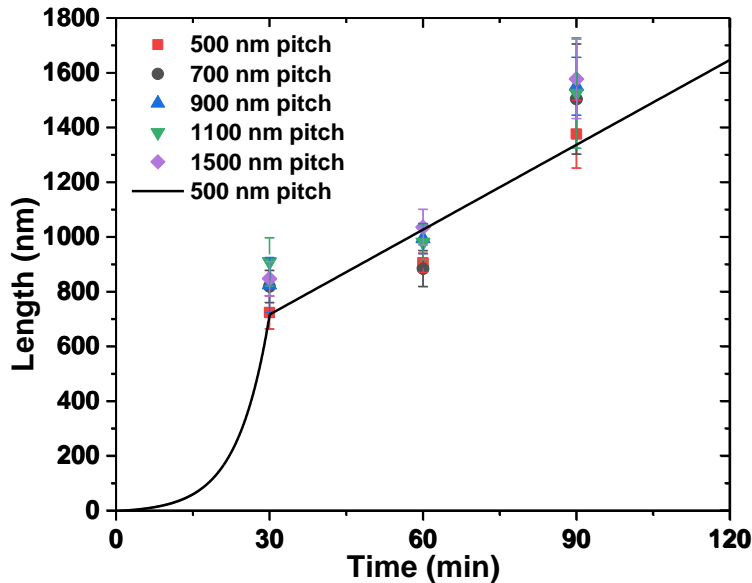
Measured geometrical parameters



Thickness from top-view images
Length and Width from tilted images (45°)

Growth modelling

InSb NF length vs growth time for different pitches



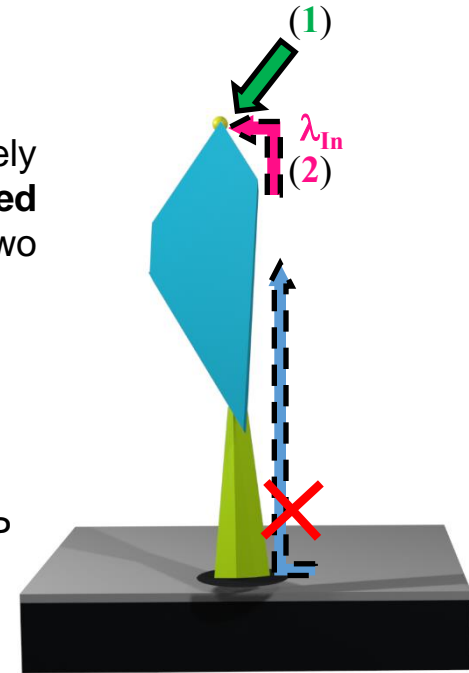
- Length evolution can be qualitatively explained by considering the **In-limited VLS axial growth** rate containing two contributions:

(1) the direct impingement

(2) In adatom diffusion on the sidewalls.

- Surface diffusion of In adatoms from the substrate can be neglected as InP NW is $\sim 1.2 \mu\text{m}$ long.

- (1) is constant, (2) is higher at $L < \lambda_{\text{In}}$
 \rightarrow For $L > \lambda_{\text{In}}$ axial growth rate becomes constant



- Axial growth rate is higher at the beginning, then decreases.
- Lower axial growth rates for smaller pitches due to shadowing or competition
- For larger pitches ($a \geq 700 \text{ nm}$) the NF lengths are almost independent of the pitch, indicating no competition above this threshold.

Fitting is done for $\lambda_{\text{In}} = 724 \text{ nm}$ at $a = 500 \text{ nm}$, with $A = 0.158 \text{ min}^{-1}$, $B = 1 \text{ nm/min}$, and $C = 0.013 \text{ min}^{-1}$

SOLUTIONS

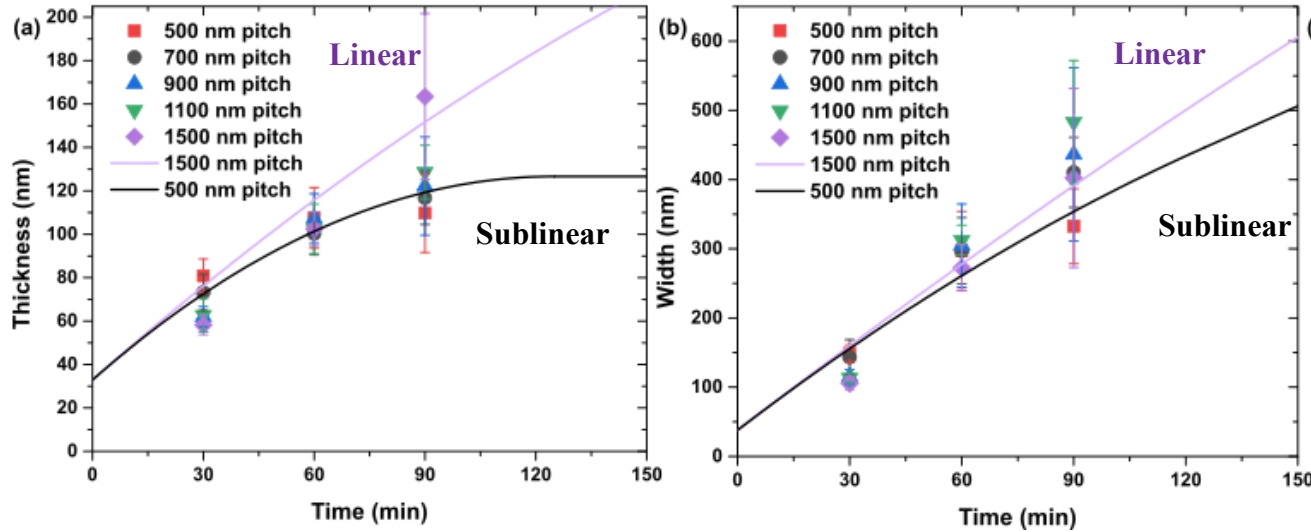
$$L = \frac{B}{A}(e^{At} - 1), L \leq \lambda_{\text{In}};$$

$$L = \lambda_{\text{In}} + (C\lambda_{\text{In}} + B)(t - t_0), L > \lambda_{\text{In}}$$

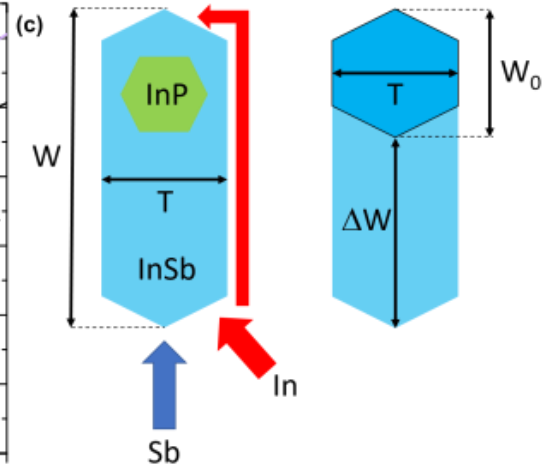
B describes direct impingement of In atoms onto catalyst surface.
 A and C stand for the efficiencies of In adatom collection from the NW sidewalls (different in the 2 stages of the growth).
 t_0 is the moment in time at which the NF length reaches λ_{In} .

Growth modelling

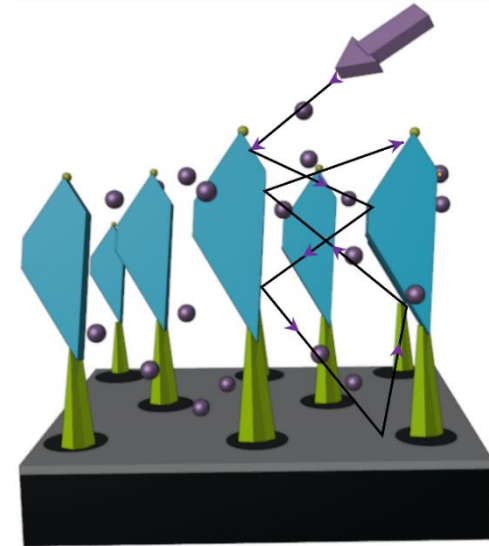
InSb NF width and thickness for different pitches



simplified 2D geometry (top-view)

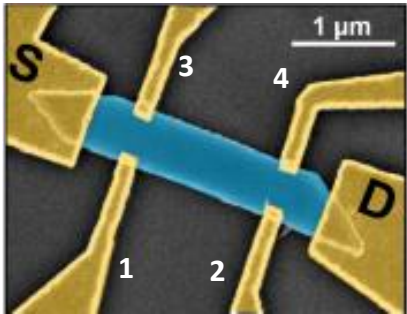


- Linear behavior for larger pitches. Sublinear for smaller pitches, T more than W .
- VS radial growth rate is Sb limited. If there were only direct Sb flux, T would be constant.
- We have to take into account **direct Sb flux** (directional) and **re-emitted Sb flux** (scattering of Sb atoms from NF sidewalls: non-directional, fully shadowed at smaller pitches)
- T increases only due to the re-emitted flux, while W has both contributions from re-emitted flux and from direct impingement of Sb flux on the 2 front facets (ΔW).
- W/T ratio can be increased by decreasing the pitch (shadowing suppresses re-emitted flux).



Thickness and width can be decoupled when re-emitted flux is completely suppressed!

NFs transport measurements

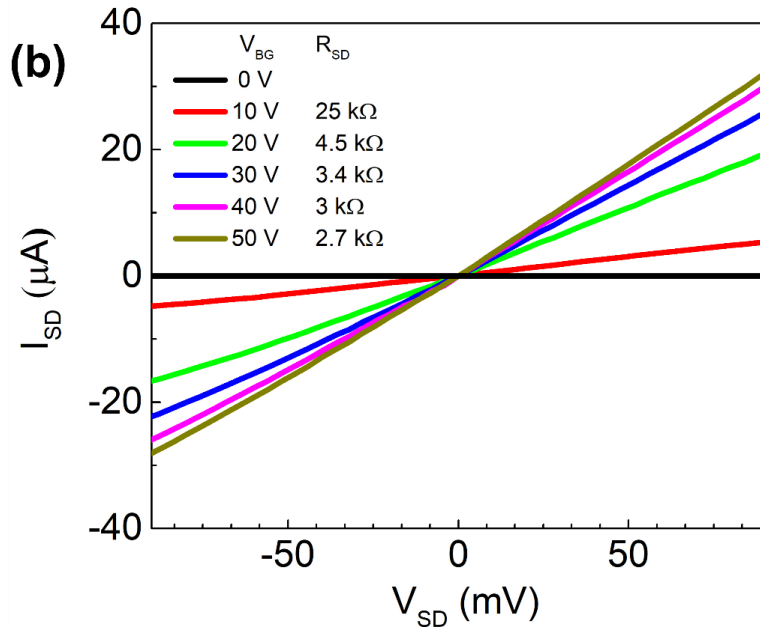


Channel width (width between contacts 1-3 and 2-4)=325 nm
Channel length (1-2 and 3-4)=1.5 μm . The NF thickness is ~ 100 nm.
Contacts: 10 nm Ti/190 nm Au
Substrate: Si/SiO₂

Hall-bar device

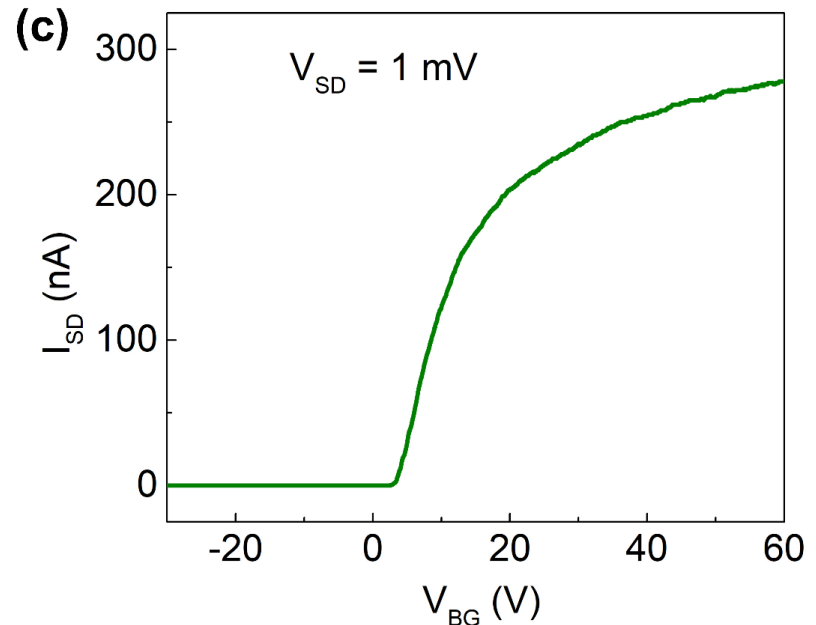
Source-drain current VS backgate voltage @ 4.2 K

$R_{SD}(\text{RT}, \text{VBG}=0 \text{ V}) = 11 \text{ k}\Omega$
 $R_{SD}(4.2\text{K}, \text{VBG}=50 \text{ V}) = 2.5 \text{ k}\Omega$



Good Ohmic contacts

n- type characteristics of InSb NFs under BG modulation

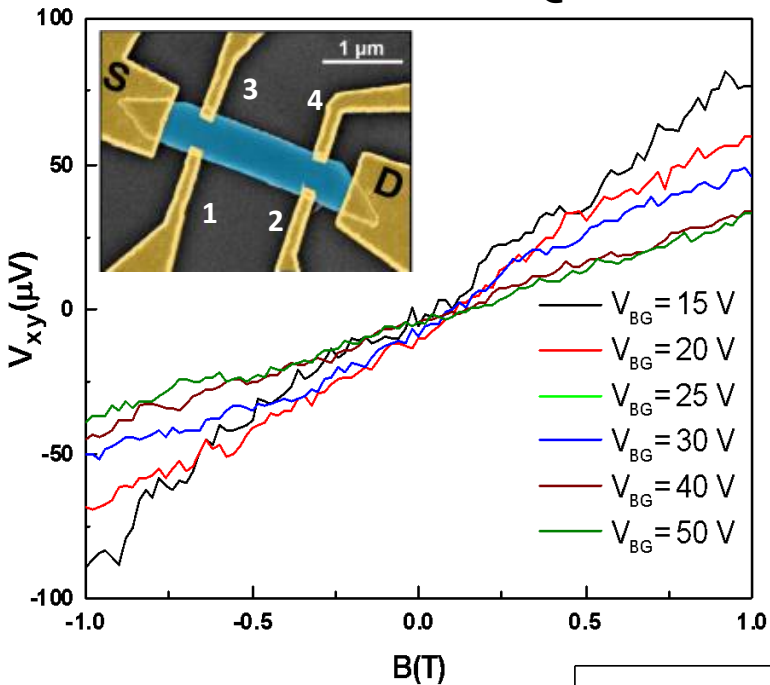


Field-effect mobility
28000 cm²/Vs

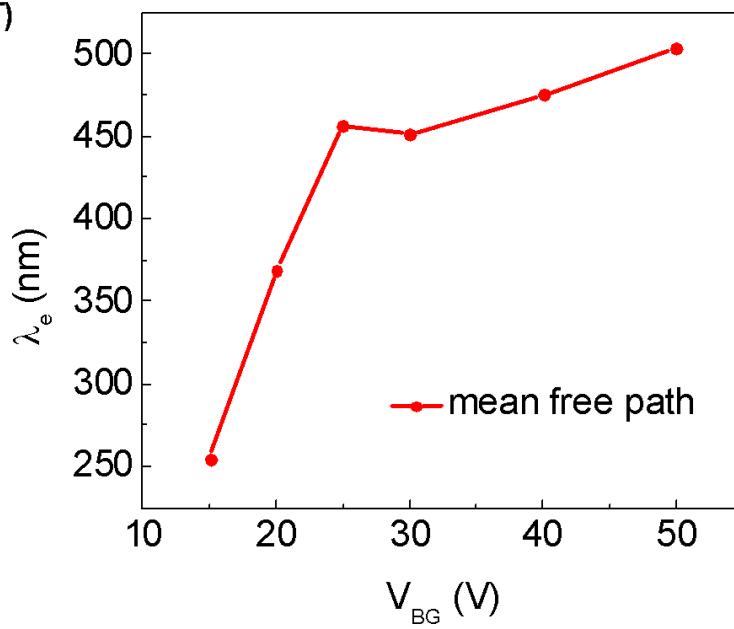
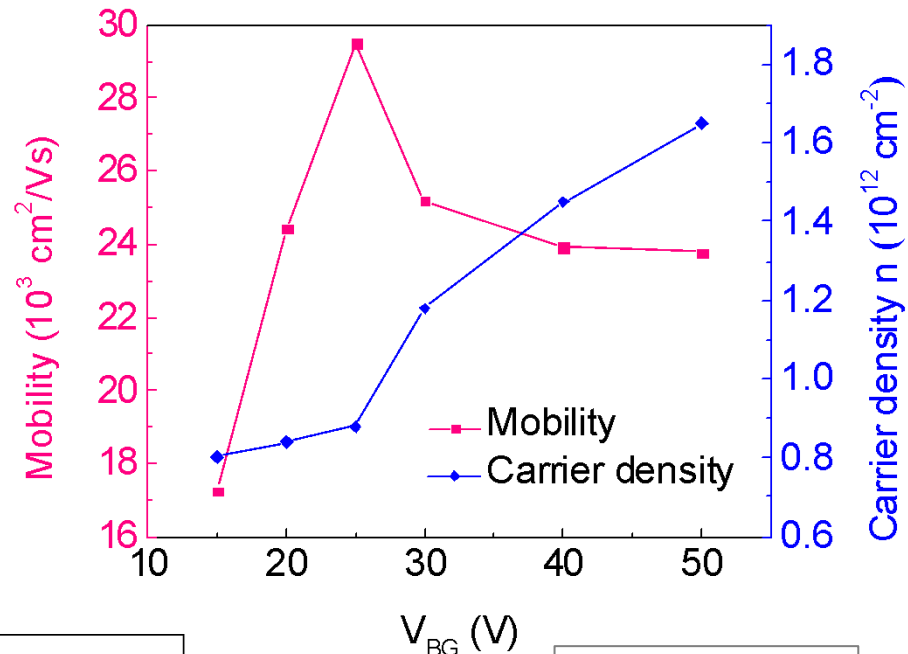
from four-probe measurement
(longitudinal voltage drop)

NFs transport measurements

Hall effect vs BG bias @ 4.2K



Electron Hall mobility = 29500 cm^2/Vs



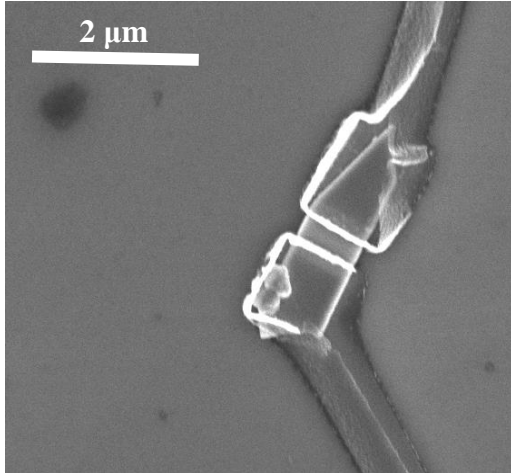
$$\mu_H = \frac{L}{W \langle V_{xx} \rangle} \left(\frac{V_{xy}}{B} \right)$$

$$n = \frac{I}{e} \left(\frac{B}{V_{xy}} \right)$$

$$\lambda_e = (\hbar\mu/e)(2\pi n)^{1/2}$$

Mean free path λ_e
up to 500 nm

Ballistic InSb NFs-based Josephson junction devices



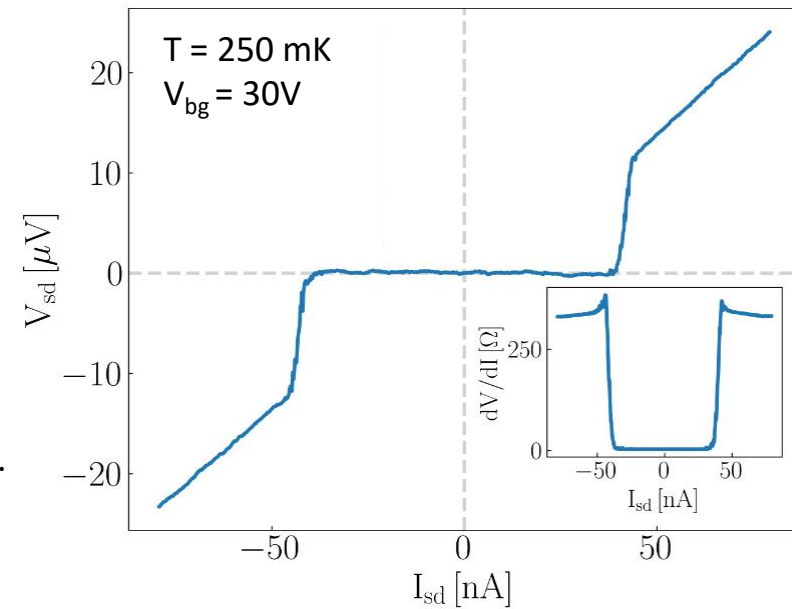
10 nm Ti/150 nm Nb
Substrate: Si/SiO₂

L = 200 nm
W = 700 nm
d = 100 nm

T_c = 8.44 K
Δ = 1.76 k_BT_c = 1.28 meV

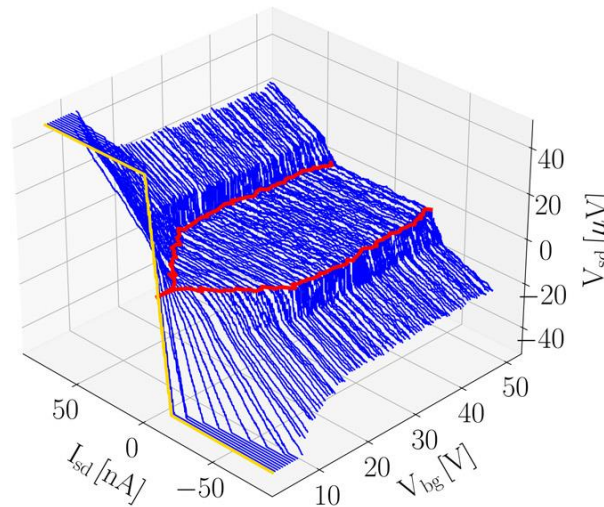
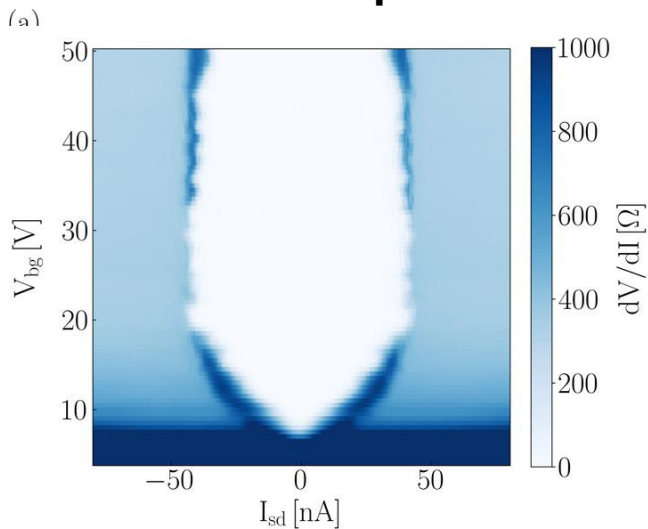
Ballistic regime! Mean free path $\lambda_e >$ length L of the junction, $\lambda_e > L$.

Voltage drop VS bias current



50 nA supercurrent

Gate tunable supercurrent



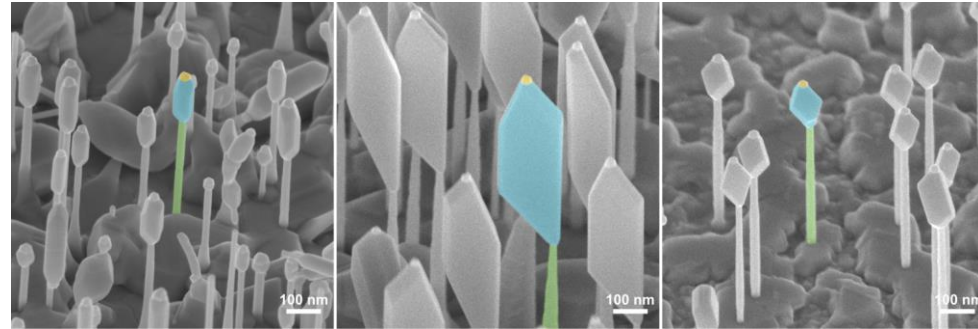
Color plot of the differential resistance

Further info:

S. Salimian et al. "Gate-controlled supercurrent in ballistic InSb nanoflag Josephson junctions" *Appl. Phys. Lett.*, 119, no. 21, 2021 doi: 10.1063/5.0071218

Conclusions

- Finding the parameters that affect axial and radial growth is important for controlling and tuning the nanostructure morphology



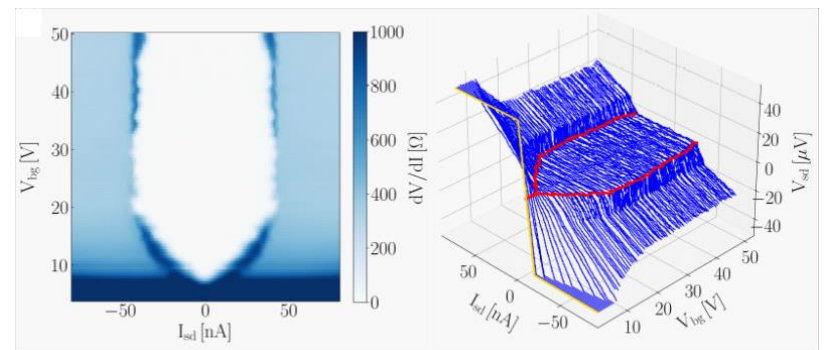
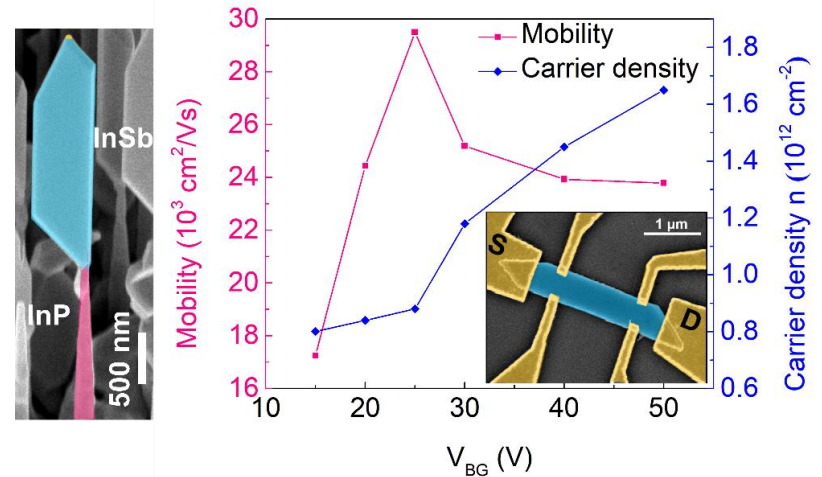
- Directional growth and more robust InP NW stems were employed to achieve large single-crystalline NFs

- A simplified growth model was developed, allowing for semi-quantitative description of the NF morphology evolution.

- Electron Hall mobility of about 29500 cm²/Vs
Mean free path upto 500 nm.

- NFs-based Josephson junction devices showed gate tunable supercurrent

- InSb NFs: versatile and convenient 2D platform for advanced quantum technologies.



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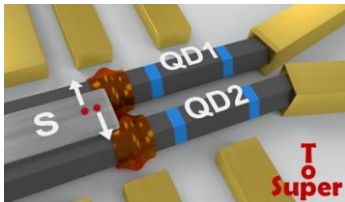


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Theoretical Modeling



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Thank you for your attention!